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## (54) RESIST COMPOSITION AND ITS PRODUCTION

(57)Abstract:

PROBLEM TO BE SOLVED: To obtain a resist compsn. which enables highly accurate processing by preparing a resist compsn. consisting of a resist and fine particles comprising aggregation of carbon atoms as the main constituent element mixed in the resist.

SOLUTION: This resist compsn. contains a resist and fine particles comprising aggregation of carbon atoms as the main constituent element mixed in the resist. Intrusion of etching reaction seeds into the film is inhibited and the etching durability of the resist film is enhanced because vacancies among the resists are filled with the fine particles, which increases the density of the resist film, and because the fine particles is composed of aggregation of carbon atoms as the main constituent element having high etching durability. Not only the enhancement of the etching durability, but intrusion of a developer into the film is inhibited and the contrast of the resist pattern is enhanced. As for the aggregation of carbon atoms as the main structural element, a fullerene can be used.

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